

Datasheet of 25Gb/s 850nm VCSEL chip

Part Number: 1104-0501XX

Doc Number: 1102-220101-01

Ownership: Components Department

Rev	Date	Description	Originator
1	2020-02-22	Initial Release	Patrick Chen

Product Description:

The chip is an 850nm top-contact, high-speed, GaAs-based Vertical Cavity Surface Emitting Laser (VCSEL), which is designed for uncooled digital applications, including 25G and 100G Ethernet, Fiber Channel and Datacenter applications.

Absolute Maximum Ratings:

Parameter	Symbol	Value	Unit	Condition
Storage Temperature	T _{st}	-40 to 90	°C	
Case Operation Temperature	T _{op}	0 to 85	°C	
Lead Solder Temperature	T _{solder}	260 °C for 10sec	°C	
Continuous Optical Power	P _{max}	8	mW	Estimated
Laser Diode Reverse Voltage	V _r	-5	V	
Laser Diode Continuous Bias Current	I _{max}	12	mA	Estimated
ESD Susceptibility (HBM)	ESD _{HBM}	100	V	Estimated

Electrical and Optical Characterizations: (T=25C unless otherwise noted)

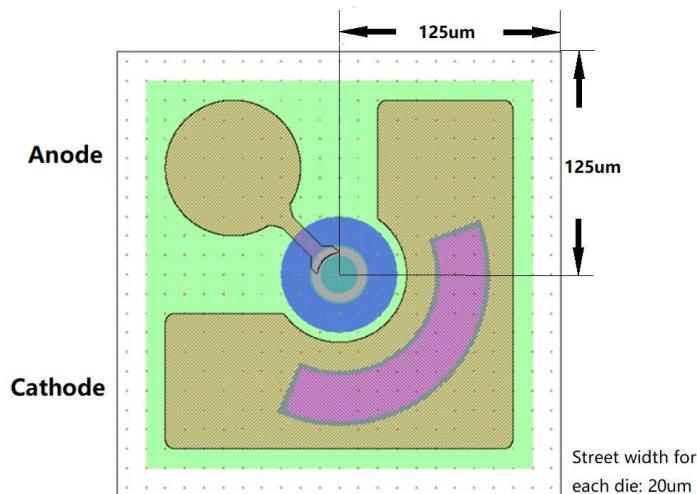
Parameter	Symbol	Min.	Typ.	Max.	Unit	Condition
Operation Temperature	T _{op}	0		85	°C	
Wavelength	λ	840	850	860	nm	CW, I _{op} =6mA, 0 to 85 °C
Output Power	P _{out}	1.5	2	4.0	mW	I _{op} =6mA, 0 to 85 °C
Threshold Current	I _{th}		0.7	1.6	mA	0 to 85 °C
Slope Efficiency	SE	0.25		0.45	mW/mA	I=I _{th} +1mA, 0 to 85 °C
Series Resistance	R _s	50		85	Ω	I _{op} =6mA, 0 to 85 °C

Spectral Width	$\Delta\lambda$			0.65	nm	$I_{op}=6\text{mA, 0 to }85^\circ\text{C}$
Temperature Dependence	$\Delta\lambda/\Delta T$		0.06		nm/°C	
Beam Divergence	θ		28	33	Degree	$I_{op}=6\text{mA, 0 to }85^\circ\text{C, full width }1/e^2$
Relative Intensity Noise	RIN		-130	-125	dB/Hz	$I_{op}=6\text{mA, 0 to }85^\circ\text{C}$
Resonance Frequency	f_r	18			GHz	$I_{op}=6\text{mA, 0 to }85^\circ\text{C}$
S21 3dB Bandwidth	BW	12.5	15		GHz	$I_{op}=6\text{mA, 0 to }85^\circ\text{C}$

Reliability Specification (Preliminary):

- End of Life Criteria: $\Delta P > 10\% @ I_{op}=6\text{mA, }85^\circ\text{C}$
- Reliability Requirement: >20 years lifetime at 55°C operation
- Reliability Test Form Factor: TO-Can
- Product Qualification (post Burn-in):
 - 3 wafers from 3 different process runs, SS=50/wafer for each step of HTOL/THB/THS
 - HTOL Condition: $85^\circ\text{C}/12\text{mA}$ for 5000 hours
 - THB: $85^\circ\text{C}/85\%\text{RH}$, 0.2A bias, 500 hours
 - THS: $85^\circ\text{C}/85\%\text{RH}$, no bias, 500 hours
- Wafer Qual Condition (post Burn-in):
 - Wearout: $85^\circ\text{C}/12\text{mA}$ for 500 hours, SS=30/wafer
 - THS Condition: $85^\circ\text{C}/85\%\text{RH}$, unbiased, 24 hours
- Burn-in Condition: $100^\circ\text{C}/10\text{mA}$ for 24 hours
- ORT (Ongoing Reliability Test): To be determined
- ESD Threshold: HBM, CDM, MM (to be measured)

Geometric Dimensions:



Parameter	Dimensions

Die Length	250 μm +/-20um
Die Width	250 μm +/-20um
Die Thickness	150 μm +/-10um
Aperture Diameter	7 μm +/- 0.5 μm
Anode Bond Pad Diameter	70 μm
Street width	40 μm , die to die

Related Documentations:

Documentation	Doc Number
Epi Structure	1102-210001-01
Process Flow	
Test Specification	
Visual Inspection Specification	